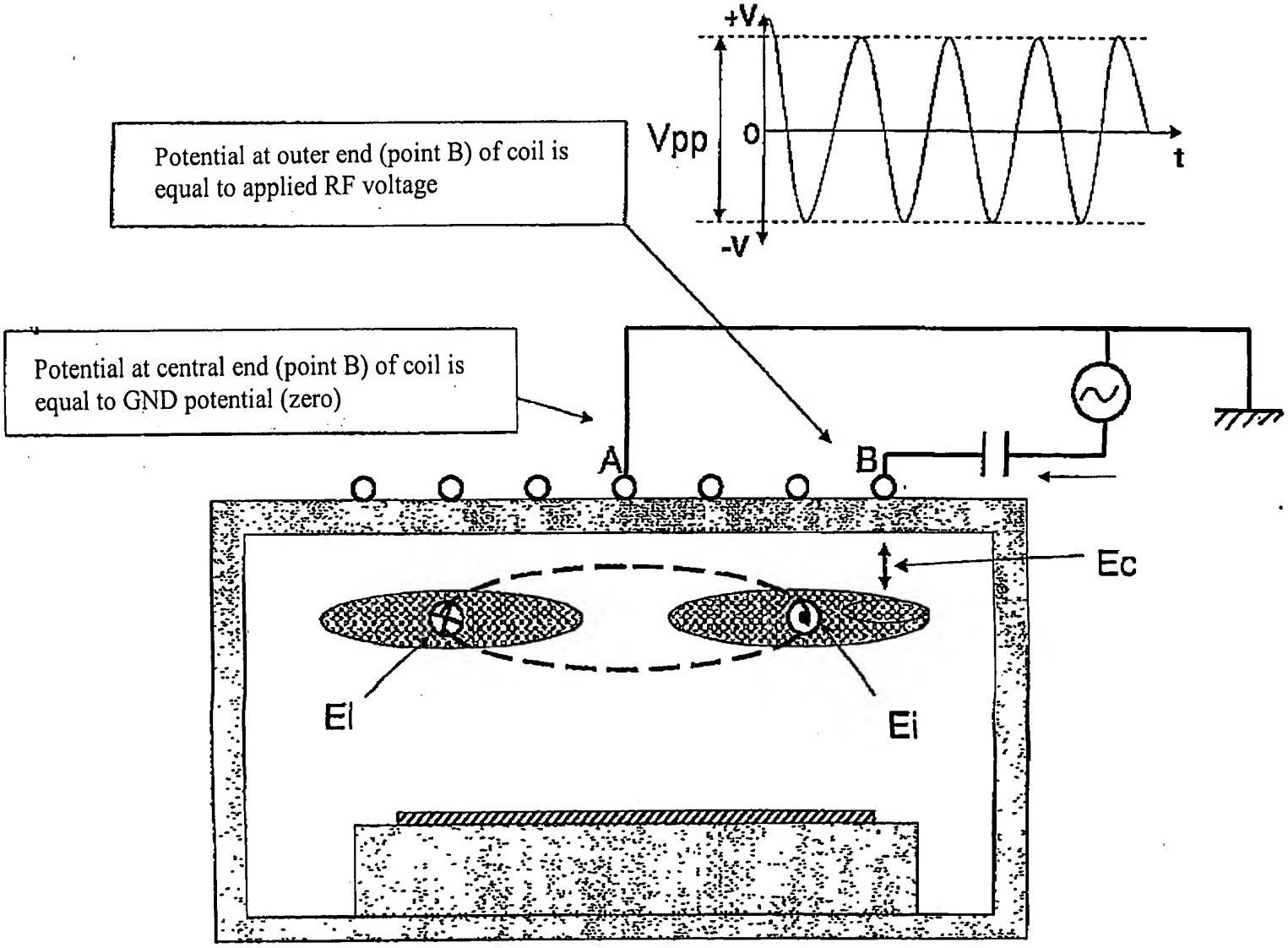
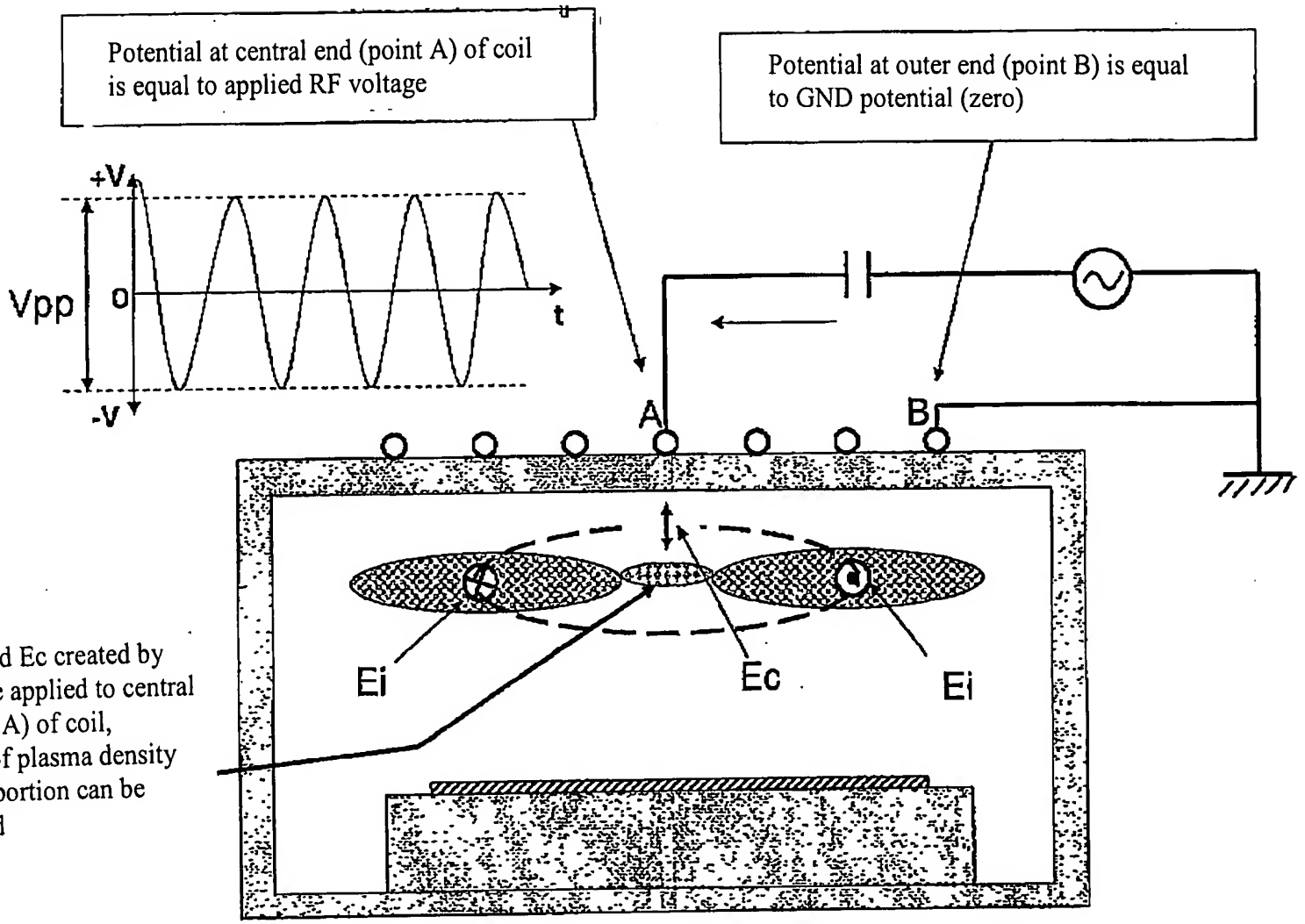
When applying RF voltage to outer end of spiral coil

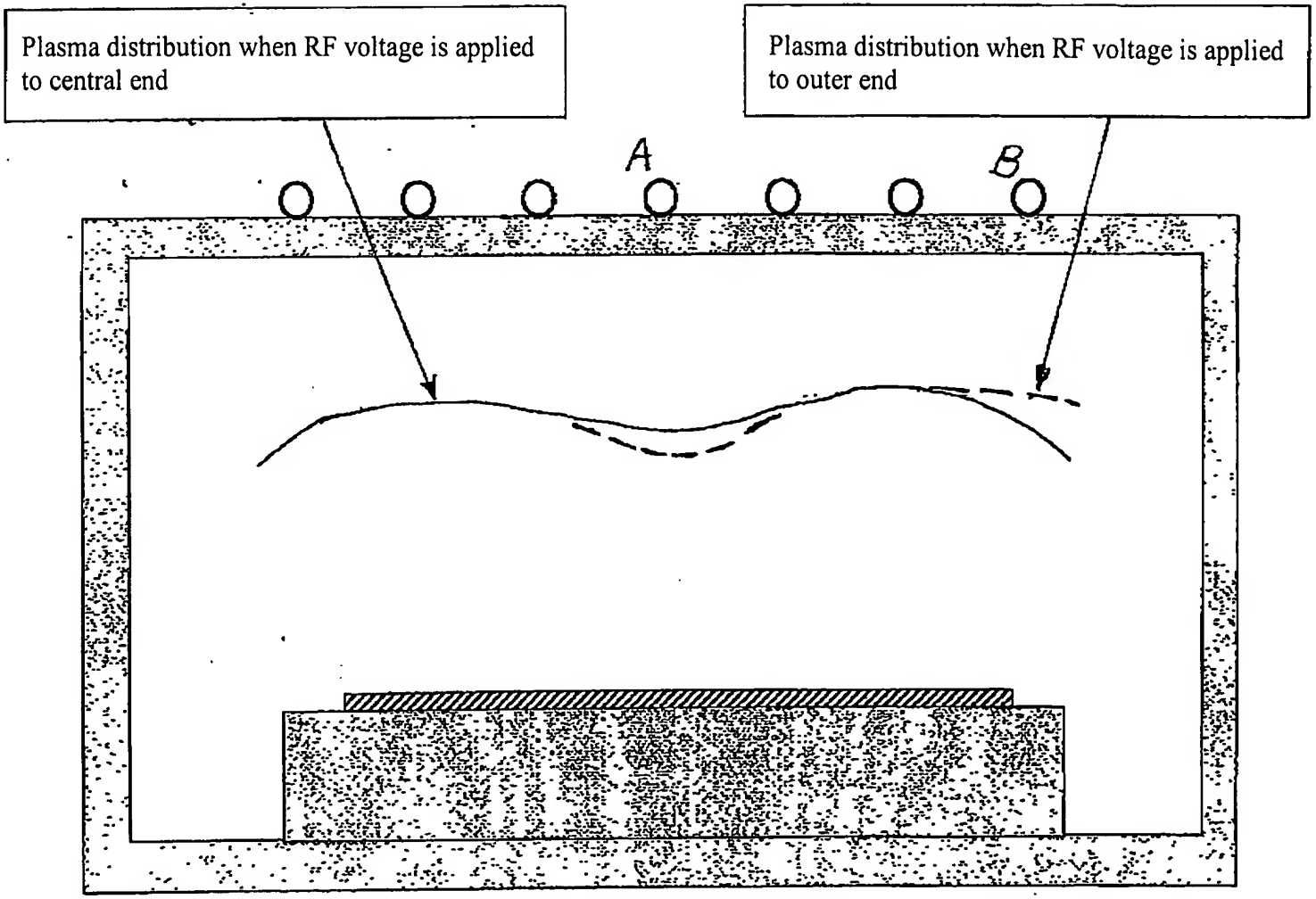


Due to field Ec created by RF voltage applied to outer end (point B) of coil, plasma distribution of outer portion may be biased

When applying RF voltage to central end of spiral coil



Due to field Ec created by RF voltage applied to central end (point A) of coil, lowering of plasma density at central portion can be suppressed



Conceptual Diagram of plasma distribution when RF voltage is applied to central end and outer end of spiral coil